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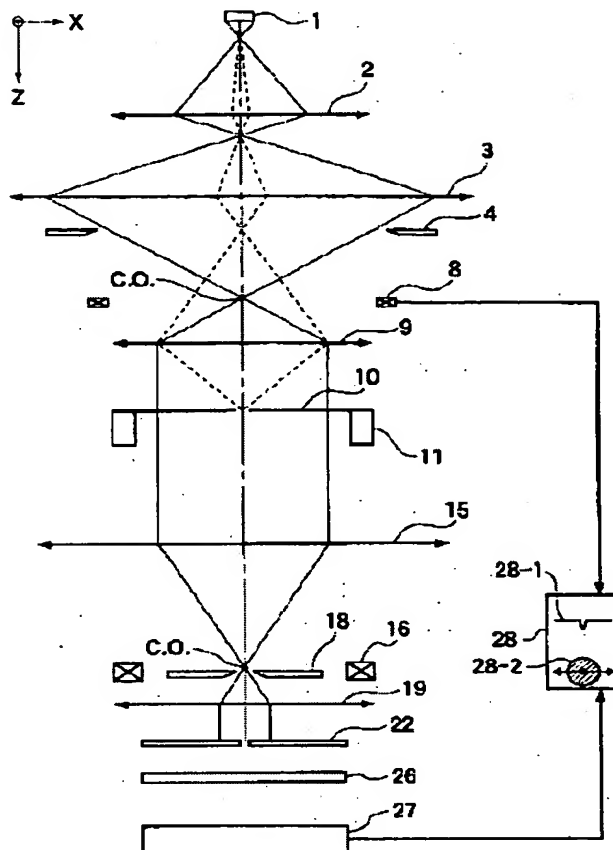
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TITLE : METHOD OF EVALUATING BEAM,  
CHARGED PARTICLE BEAM  
EXPOSURE SYSTEM, AND METHOD  
OF MANUFACTURING DEVICE



ABSTRACT : PROBLEM TO BE SOLVED: To provide a method of evaluating beam, etc., by which the intensity distribution of a beam can be evaluated with accuracy.

SOLUTION: A pinhole is provided in the central part of one visual field of a reticle 10. A hole plate 22 is made of copper, etc., and has a hole of about 10  $\mu\text{m}$  square in its central part. A monitor 17 is arranged between a photomultiplier 27 and an illuminating beam deflector 8. After the beam passes through the hole plate 22, the beam comes into collision with a scintillator 26 and emits light. The light is converted into electric signals by means of the photomultiplier 27 and the signals are inputted to the monitor 28. The signals are displayed on the monitor 28 as an image 28-2 when the luminance of the monitor 28 is modulated or as an intensity distribution signal 28-1.

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